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In the Claims:

## 1. (Canceled)

2. (Currently Amended) The method according to claim 1 A method for forming a ruthenium film, the method comprising supplying a two  $\beta$  -diketones-coordinated ruthenium complex as a ruthenium source and oxygen onto a substrate and depositing the ruthenium film using chemical vapor deposition (CVD), wherein the ruthenium source is a two  $\beta$  -diketones and one diene-coordinated ruthenium complex as represented by the formula 1:

$$R_2$$
 $R_3$ 
 $R_4$ 
 $R_5$ 
 $R_2$ 
 $R_1$ 
 $R_1$ 
 $R_2$ 
 $R_1$ 
 $R_2$ 
 $R_1$ 
 $R_2$ 
 $R_1$ 

wherein  $R_1$  and  $R_2$  are alkyl groups; the total carbon number of  $R_1$  and  $R_2$  is 3 to 5; and  $R_3$ ,  $R_4$  and  $R_5$  are interconnected to each other to form a chain.

- 3. (Original) The method according to claim 2, wherein the diene is 1,4-cyclohexadiene, norbornadiene, or 1,5-cyclooctadiene.
- 4. (Original) The method according to claim 2, wherein  $R_1$  and  $R_2$  are asymmetric.

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5. (Currently Amended) The method according to claim 1-A method for forming a ruthenium film, the method comprising supplying a two  $\beta$ -diketones-coordinated ruthenium complex as a ruthenium source and oxygen onto a substrate and depositing the ruthenium film using chemical vapor deposition (CVD), wherein the ruthenium source is a two  $\beta$ -diketones and one diamine-coordinated ruthenium complex as represented by the formula 2:

$$R_{10}$$
 $R_{10}$ 
 $R$ 

wherein  $R_1$  and  $R_2$  are alkyl groups; the total carbon number of  $R_1$  and  $R_2$  is 2 to 5;  $R_6$ ,  $R_7$ ,  $R_8$ ,  $R_9$ ,  $R_{10}$  and  $R_{11}$  are independently hydrogen or alkyl groups; and the total carbon number of  $R_6$ ,  $R_7$ ,  $R_8$ ,  $R_9$ ,  $R_{10}$  and  $R_{11}$  is 2 to 8.

- 6. (Original) The method according to claim 5, wherein the diamine is N,N,N',N'-tetramethylethylenediamine.
- 7. (Original) The method according to claim 5, wherein  $R_1$  and  $R_2$  are asymmetric.
- 8. (Currently Amended) The method according to claim 1-A method for forming a ruthenium film, the method comprising supplying a two  $\beta$  -diketones-coordinated ruthenium complex as a ruthenium source and oxygen onto a substrate and depositing the ruthenium film using chemical vapor deposition (CVD), wherein the ruthenium source is a two  $\beta$  -diketones and two organic ligands-coordinated ruthenium complex as represented by the formula 3:

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$$R_{12}$$
 $R_{12}$ 
 $R_{12}$ 
 $R_{12}$ 
 $R_{12}$ 
 $R_{13}$ 
 $R_{14}$ 
 $R_{15}$ 
 $R_{15}$ 

wherein  $R_1$  and  $R_2$  are alkyl groups; the total carbon number of  $R_1$  and  $R_2$  is 2 to 5; and two  $R_{12}$  groups are olefin, amine, nitrile or carbonyl.

- 9. (Original) The method according to claim 8, wherein the olefin is ethylene, propylene, 2-methylpropylene, butyl, or 1,3-butadiene.
- 10. (Original) The method according to claim 9, wherein the amine is trimethylamine or triethylamine.
- 11. (Original) The method according to claim 10, wherein the nitirile is acetonitrile or acrylonitrile.
- 12. (Original) The method according to claim 8, wherein the two  $\beta$  -diketones are 2,4-hexanedione, 5-methyl-2,4-hexanedione, 2,4-heptanedione, 5-methyl-2,4-heptanedione, 6-methyl-2,4-heptanedione, or 2,4-octanedione.
- 13. (Currently Amended) The method according to claim-1-A method for forming a ruthenium film, the method comprising supplying a two  $\beta$  -diketones-coordinated ruthenium complex as a ruthenium source and oxygen onto a substrate and depositing the ruthenium film using chemical vapor deposition (CVD), wherein the ruthenium source is bis(isoheptane-2,4-dionato)norbornadiene ruthenium (Ru(C<sub>7</sub>H<sub>8</sub>)(C<sub>7</sub>H<sub>11</sub>O<sub>2</sub>)<sub>2</sub>).

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## 14-19. (Canceled)

20. (Currently Amended) The method according to claim 19A method for forming a ruthenium film, the method comprising supplying a two  $\beta$  -diketones-coordinated ruthenium complex as a ruthenium source at a flow rate of 0.2-1 ccm and oxygen at a flow rate of 20-60 sccm, and depositing the ruthenium film using CVD, wherein the ruthenium source is a two  $\beta$  -diketones and one diene-coordinated ruthenium complex as represented by the formula 1:

$$R_2$$
 $R_3$ 
 $R_4$ 
 $R_5$ 
 $R_2$ 
 $R_1$ 
 $R_1$ 
 $R_2$ 
 $R_1$ 
 $R_2$ 
 $R_1$ 
 $R_2$ 
 $R_1$ 

wherein  $R_1$  and  $R_2$  are alkyl groups; the total carbon number of  $R_1$  and  $R_2$  is 3 to 5; and  $R_3$ ,  $R_4$  and  $R_5$  are interconnected to each other to form a chain.

- 21. (Original) The method according to claim 20, wherein the diene is 1,4-cyclohexadiene, norbornadiene, or 1,5-cyclooctadiene.
- 22. (Original) The method according to claim 20, wherein  $R_1$  and  $R_2$  are asymmetric.
- 23. (Currently Amended) The method according to claim 19 A method for forming a ruthenium film, the method comprising supplying a two β -diketones-coordinated ruthenium complex as a ruthenium source at a flow rate of 0.2-1 ccm and oxygen at a flow rate of 20-60

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sccm, and depositing the ruthenium film using CVD, wherein the ruthenium source is a two  $\beta$  -diketones and one diamine-coordinated ruthenium complex as represented by the formula 2:

$$R_{10}$$
 $R_{10}$ 
 $R$ 

wherein,  $R_1$  and  $R_2$  are alkyl groups; the total carbon number of  $R_1$  and  $R_2$  is 2 to 5;  $R_6$ ,  $R_7$ ,  $R_8$ ,  $R_9$ ,  $R_{10}$  and  $R_{11}$  are independently hydrogen or alkyl groups; and the total carbon number of  $R_6$ ,  $R_7$ ,  $R_8$ ,  $R_9$ ,  $R_{10}$  and  $R_{11}$  is 2 to 8.

- 24. (Original) 'The method according to claim 23, wherein the diamine is N,N,N',N'-tetramethylenediamine.
- 25. (Original) The method according to claim 23, wherein  $R_1$  and  $R_2$  are asymmetric.
- 26. (Currently Amended) The method according to claim 19A method for forming a ruthenium film, the method comprising supplying a two  $\beta$  -diketones-coordinated ruthenium complex as a ruthenium source at a flow rate of 0.2-1 ccm and oxygen at a flow rate of 20-60 sccm, and depositing the ruthenium film using CVD, wherein the ruthenium source is a two  $\beta$  -diketones and two organic ligands-coordinated ruthenium complex as represented by the formula 3:

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$$R_{12}$$
 $R_{12}$ 
 $R_{12}$ 
 $R_{12}$ 
 $R_{12}$ 
 $R_{13}$ 
 $R_{14}$ 
 $R_{15}$ 
 $R_{15}$ 

wherein  $R_1$  and  $R_2$  are alkyl groups; the total carbon number of  $R_1$  and  $R_2$  is 2 to 5; and two  $R_{12}$  groups are olefin, amine, nitrile or carbonyl.

- 27. (Original) The method according to claim 26, wherein the olefin is ethylene, propylene, 2-methylpropylene, butyl, or 1,3-butadiene.
- 28. (Original) The method according to claim 27, wherein the amine is trimethylamine or triethylamine.
- 29. (Original) The method according to claim 28, wherein the nitirile is acetonitrile or acrylonitrile.
- 30. (Original) The method according to claim 26, wherein the two  $\beta$  -diketones are 2,4-hexanedione, 5-methyl-2,4-hexanedione, 2,4-heptanedione, 5-methyl-2,4-heptanedione, or 2,4-octanedione.
- 31. (Currently Amended) The method according to claim 19A method for forming a ruthenium film, the method comprising supplying a two β -diketones-coordinated ruthenium complex as a ruthenium source at a flow rate of 0.2-1 ccm and oxygen at a flow rate of 20-60 sccm, and depositing the ruthenium film using CVD, wherein the ruthenium so urce is bis(isoheptane-2,4-dionato)norbornadiene ruthenium.

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32-34. (Canceled)

- 35. (Original) A method for forming a ruthenium film, the method comprising supplying bis(isoheptane-2,4-dionato)norbornadiene ruthenium at a flow rate of 0.2-1 ccm and oxygen at a flow rate of 20-60 sccm and depositing the ruthenium film at a temperature of 330-430°C under a pressure of 0.5-5 Torr using CVD.
- 36. (Original) The method according to claim 35, wherein the depositing of the ruthenium film includes supplying an inert gas, including nitrogen and argon, onto the substrate.

37. - 52. (Canceled)